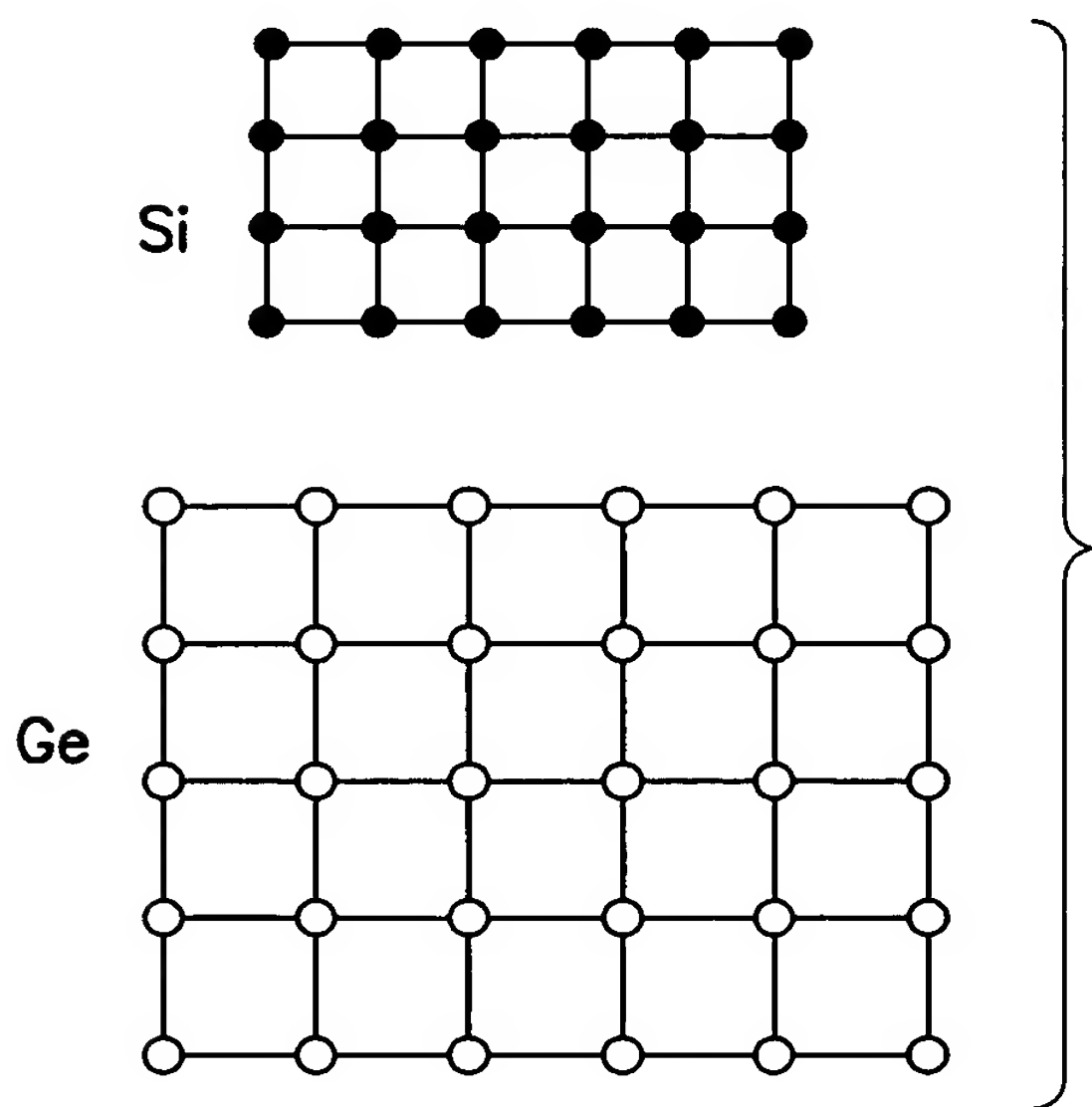
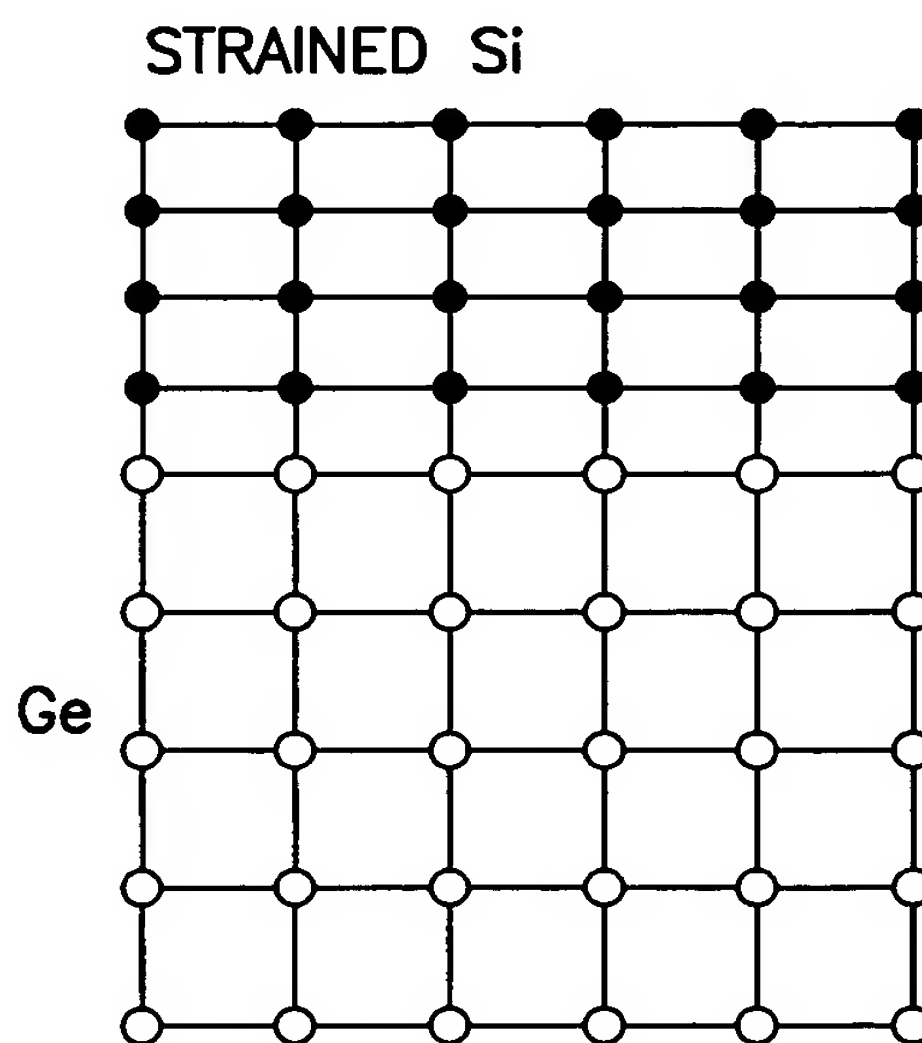


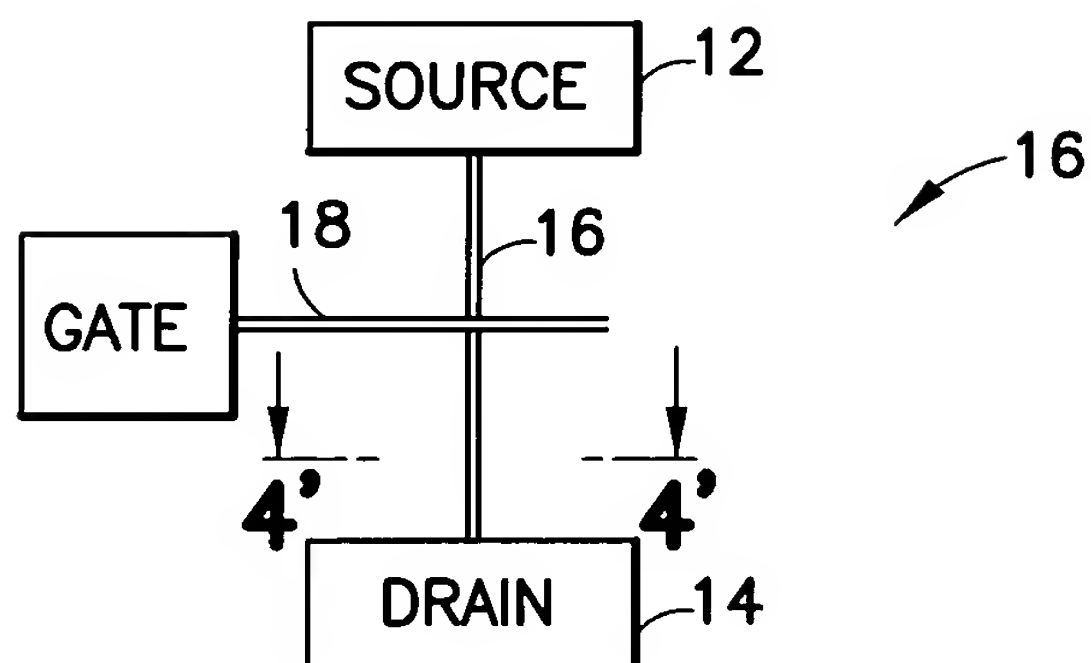
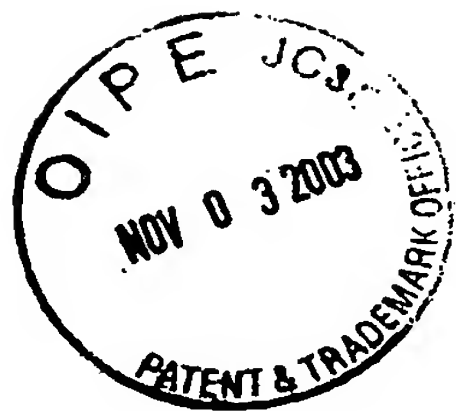
**FIG.1**  
PRIOR ART



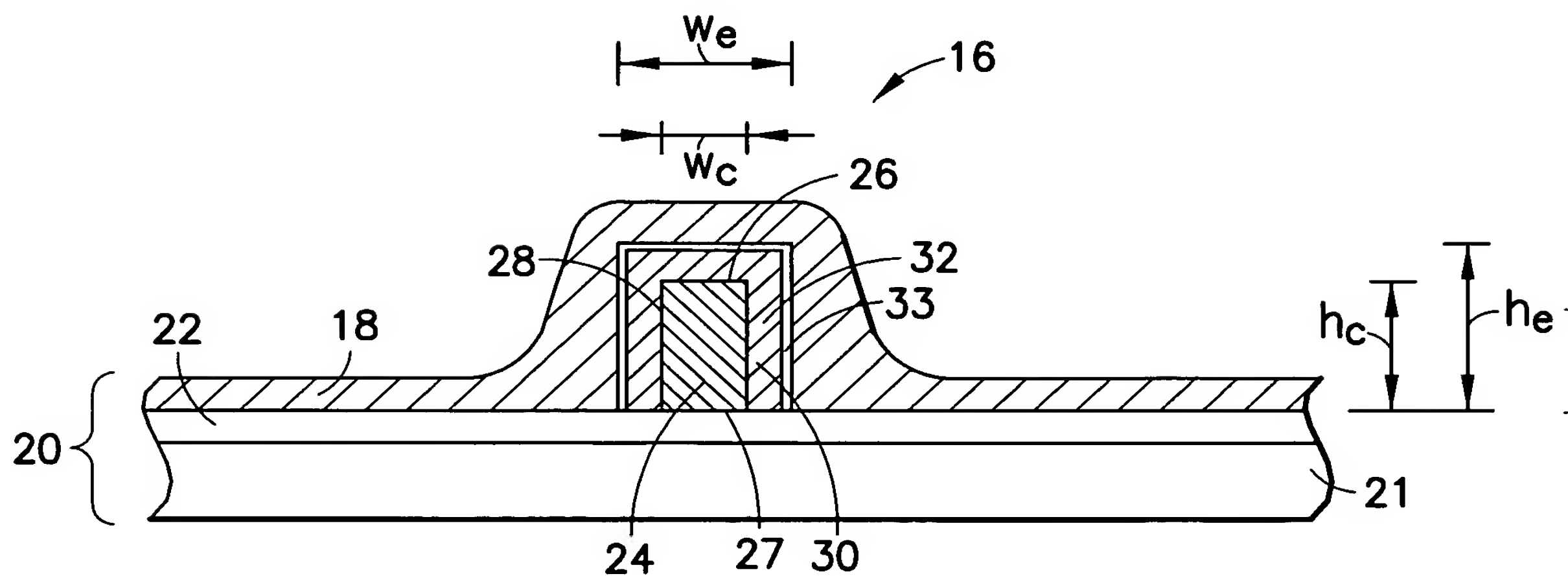
**FIG.2a**  
PRIOR ART



**FIG.2b**  
PRIOR ART



**FIG.3**



**FIG.4**



<u>38</u>	SILICON
<u>22</u>	BURIED OXIDE LAYER (BOX)
<u>20</u>	SUBSTRATE

FIG.5a

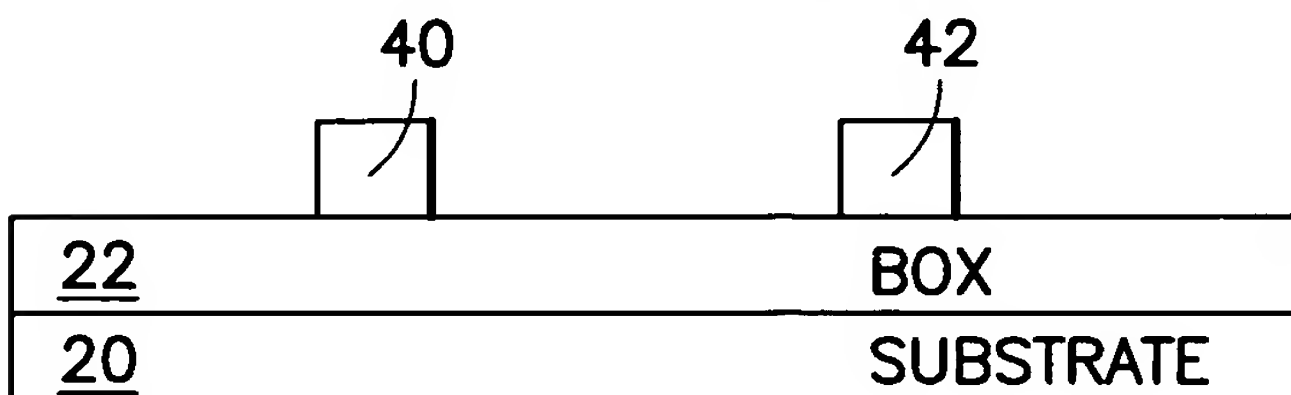


FIG.5b

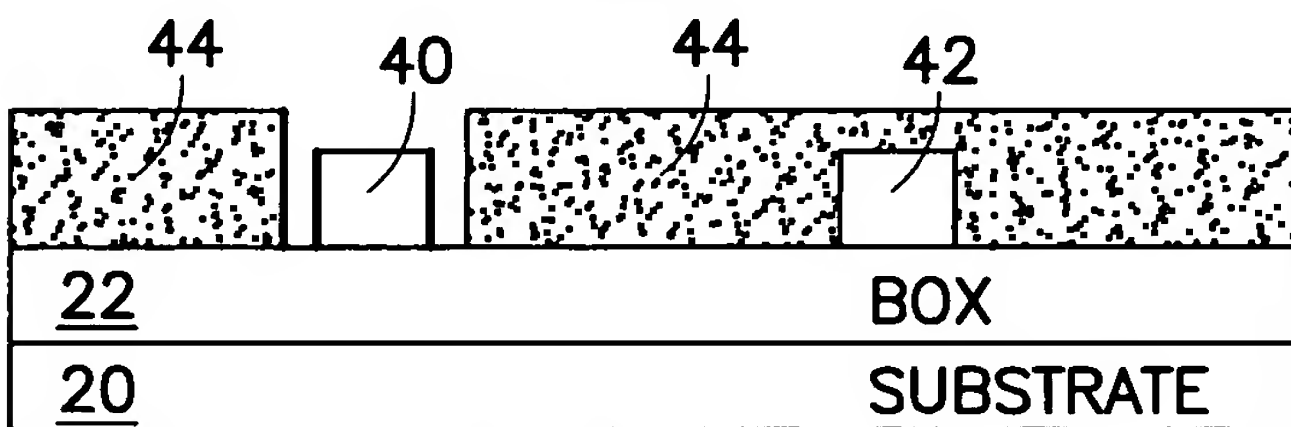


FIG.5c

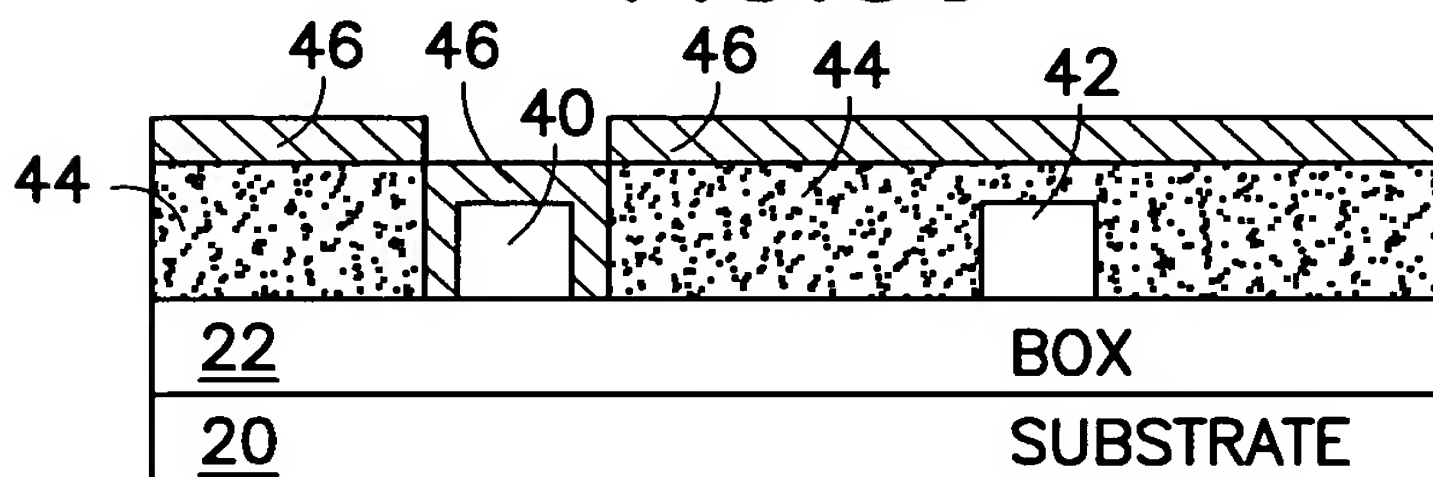


FIG.5d

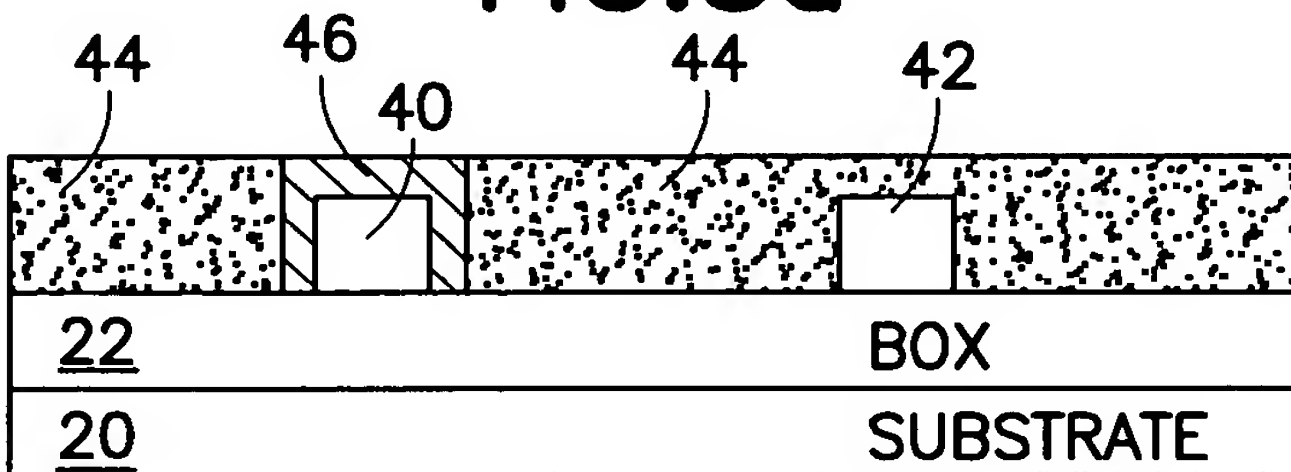


FIG.5e

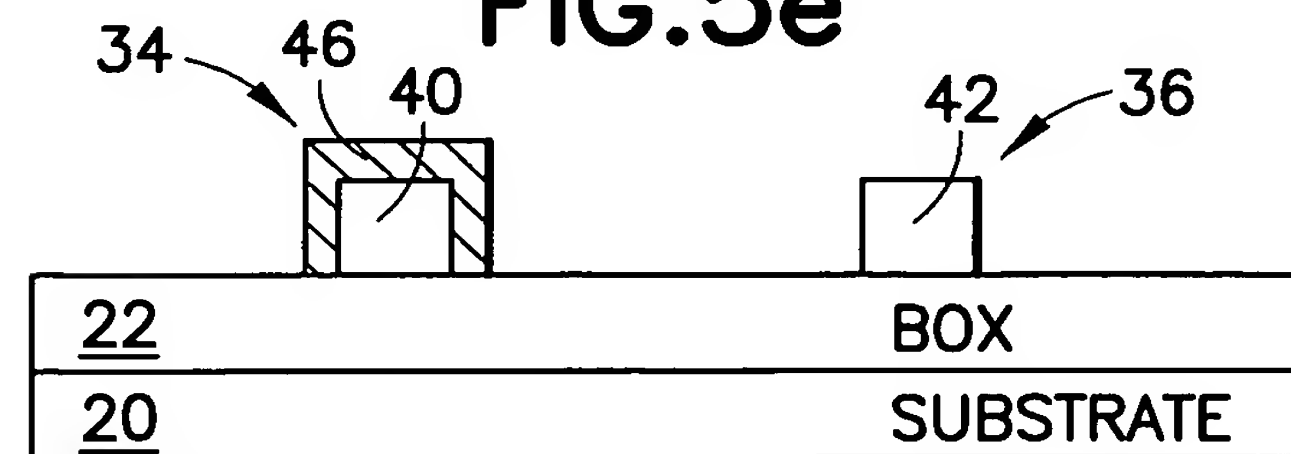


FIG.5f

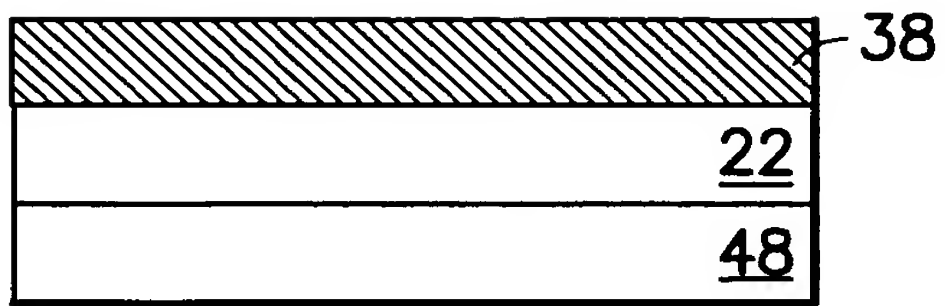


FIG. 6a

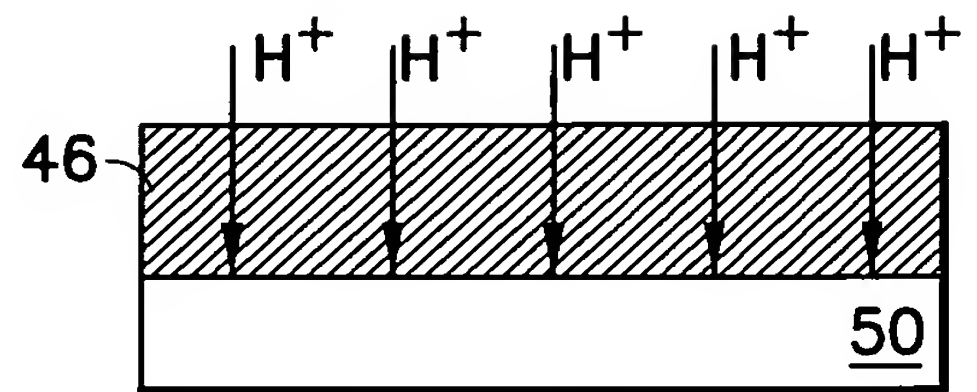


FIG. 6c

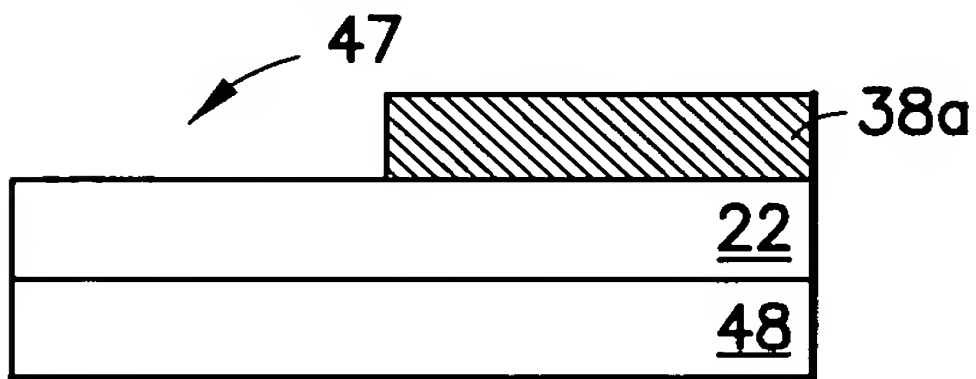


FIG. 6b

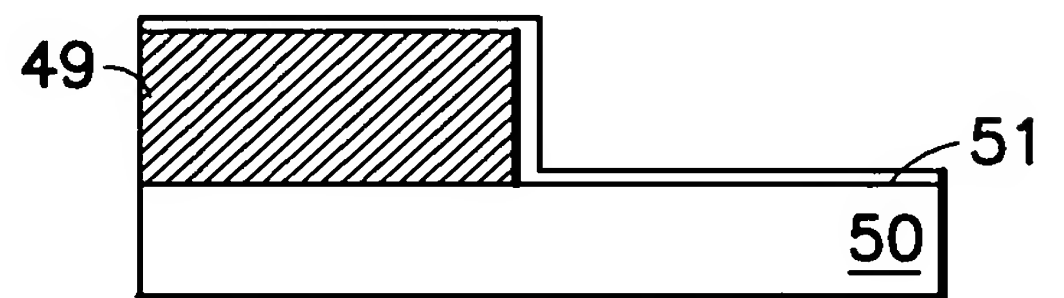


FIG. 6d

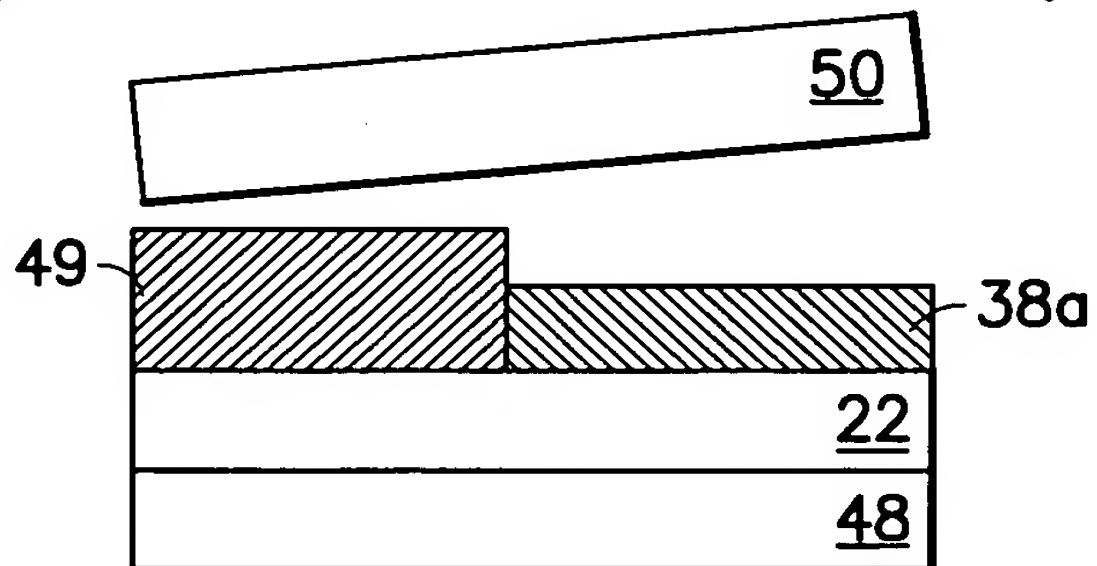


FIG. 6e

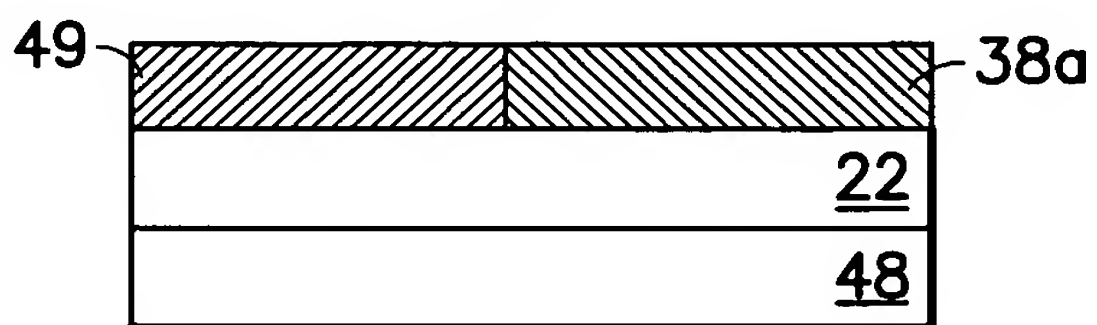


FIG. 6f

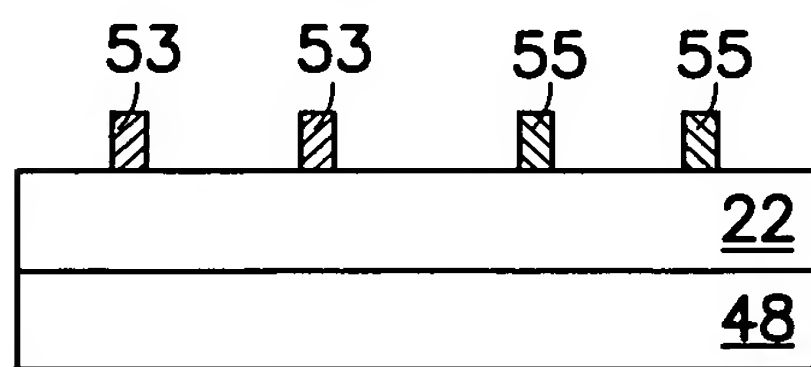


FIG. 6g

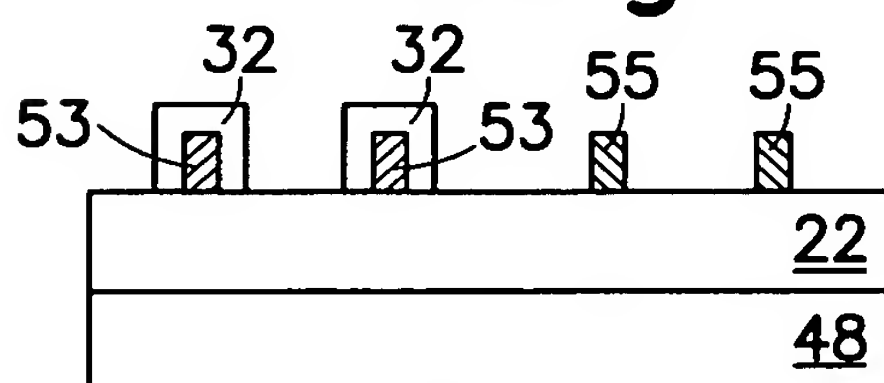


FIG. 6h

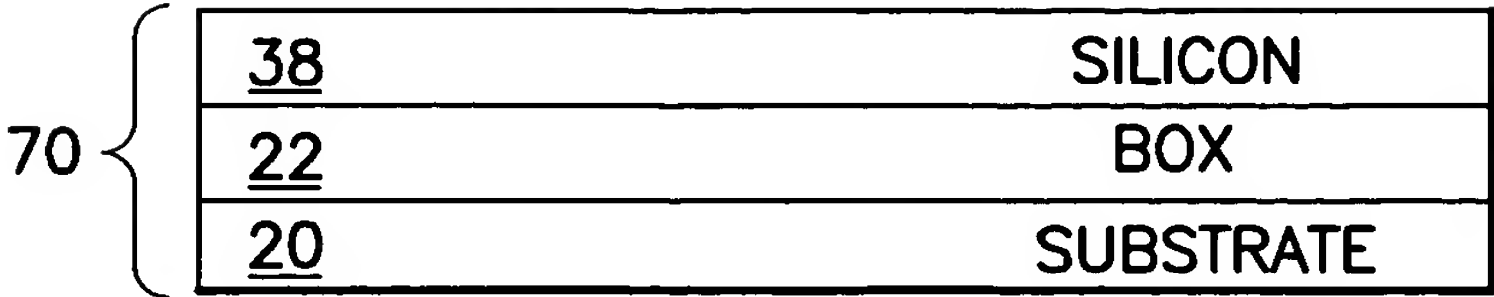


FIG.7a

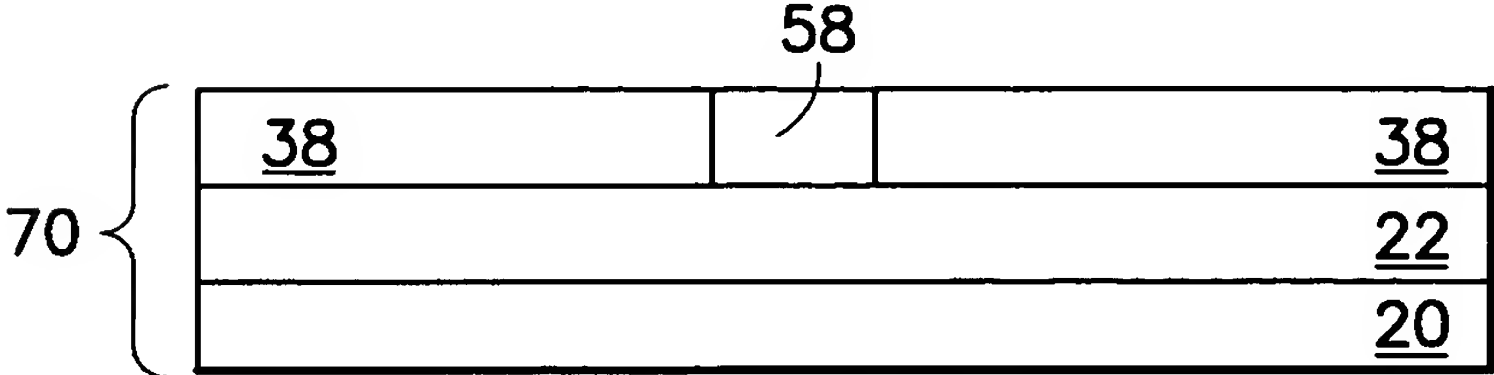


FIG.7b

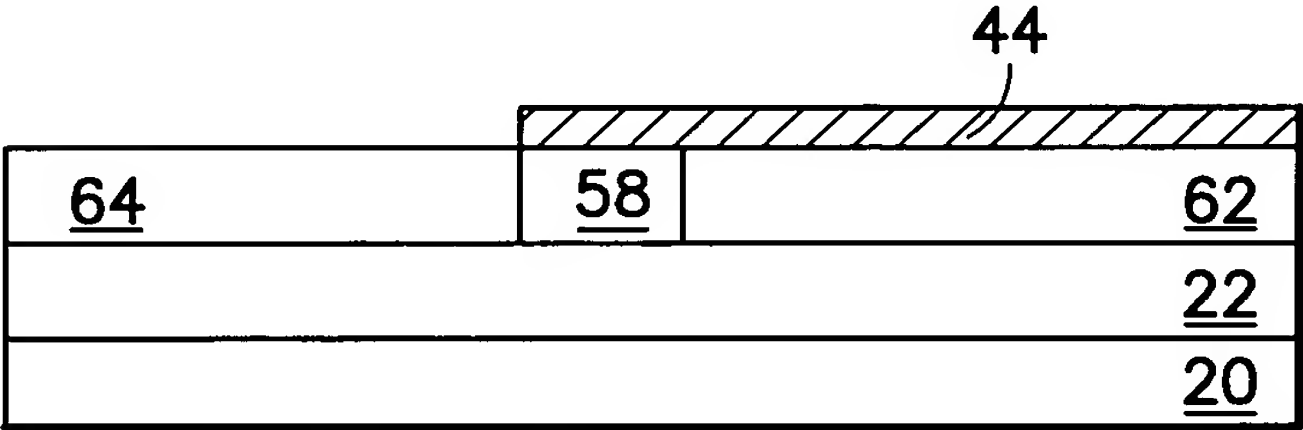


FIG.7c

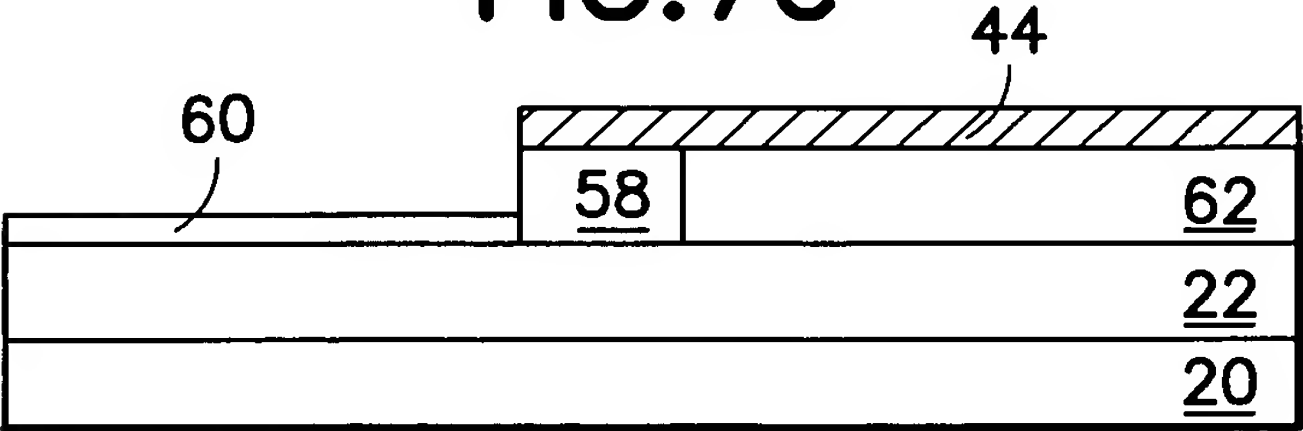


FIG.7d

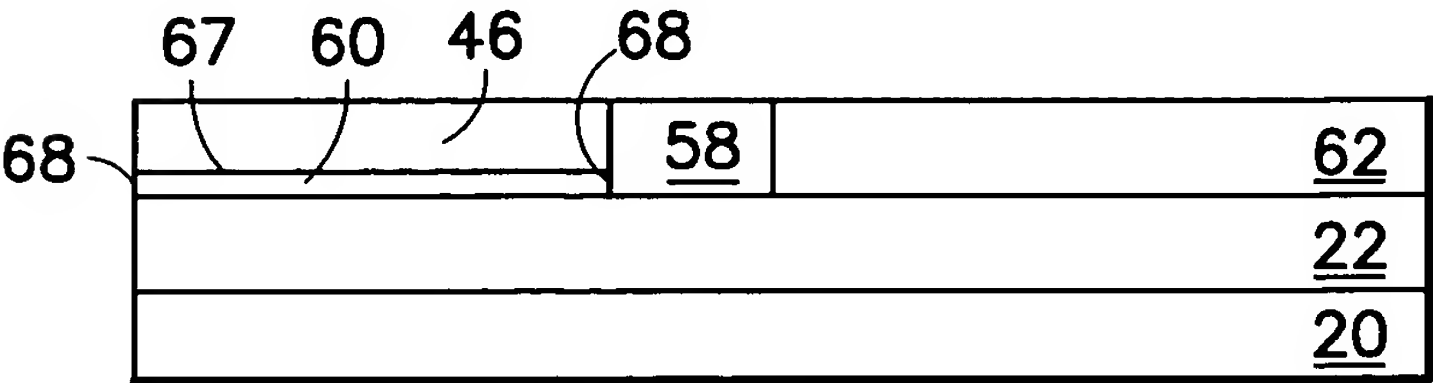
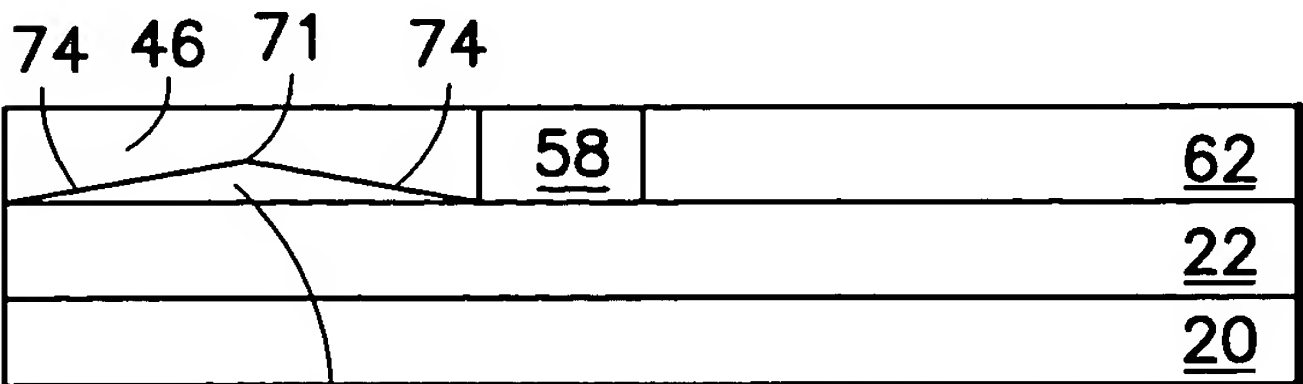


FIG.7e



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FIG.7f

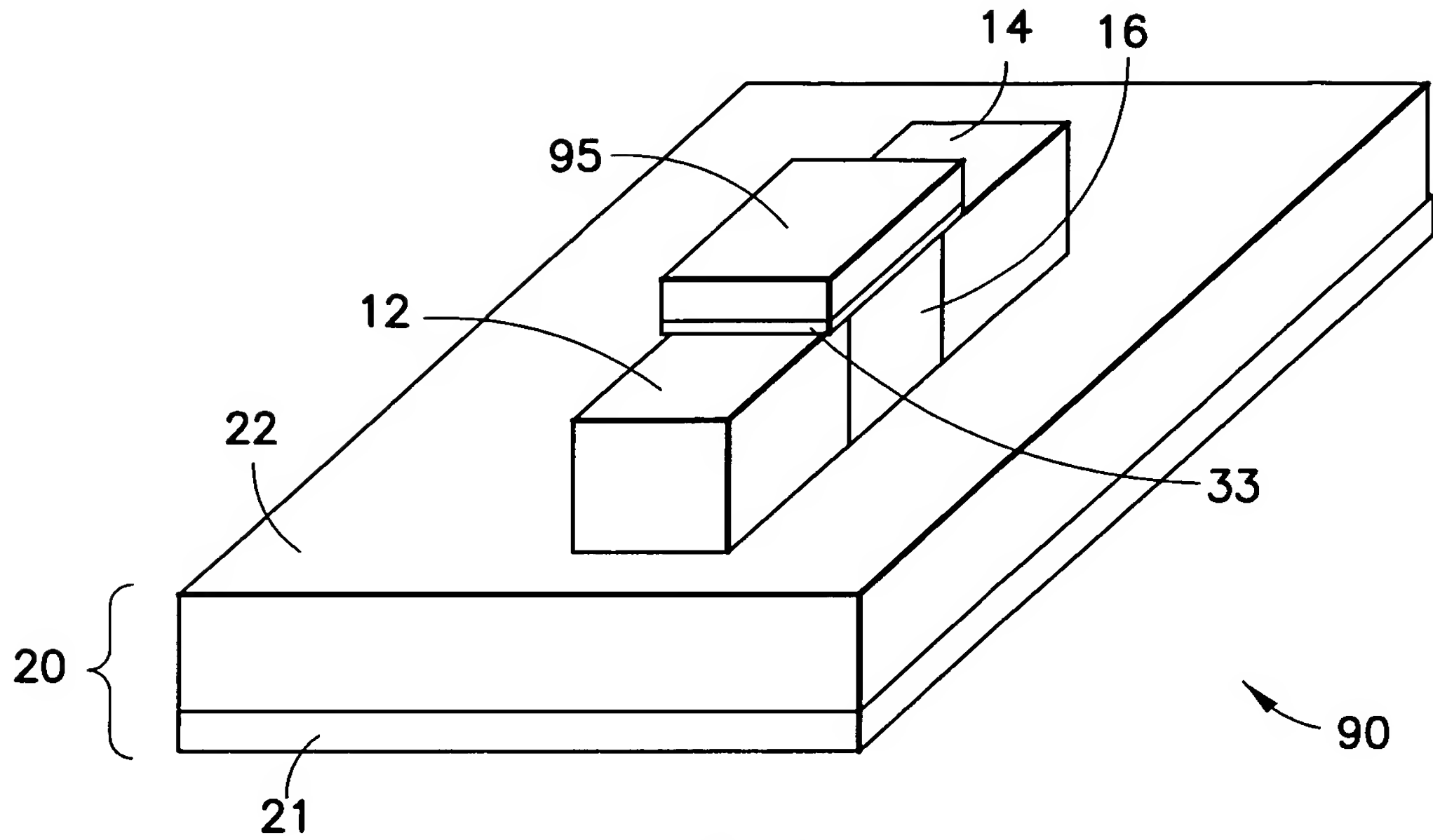


FIG. 8A

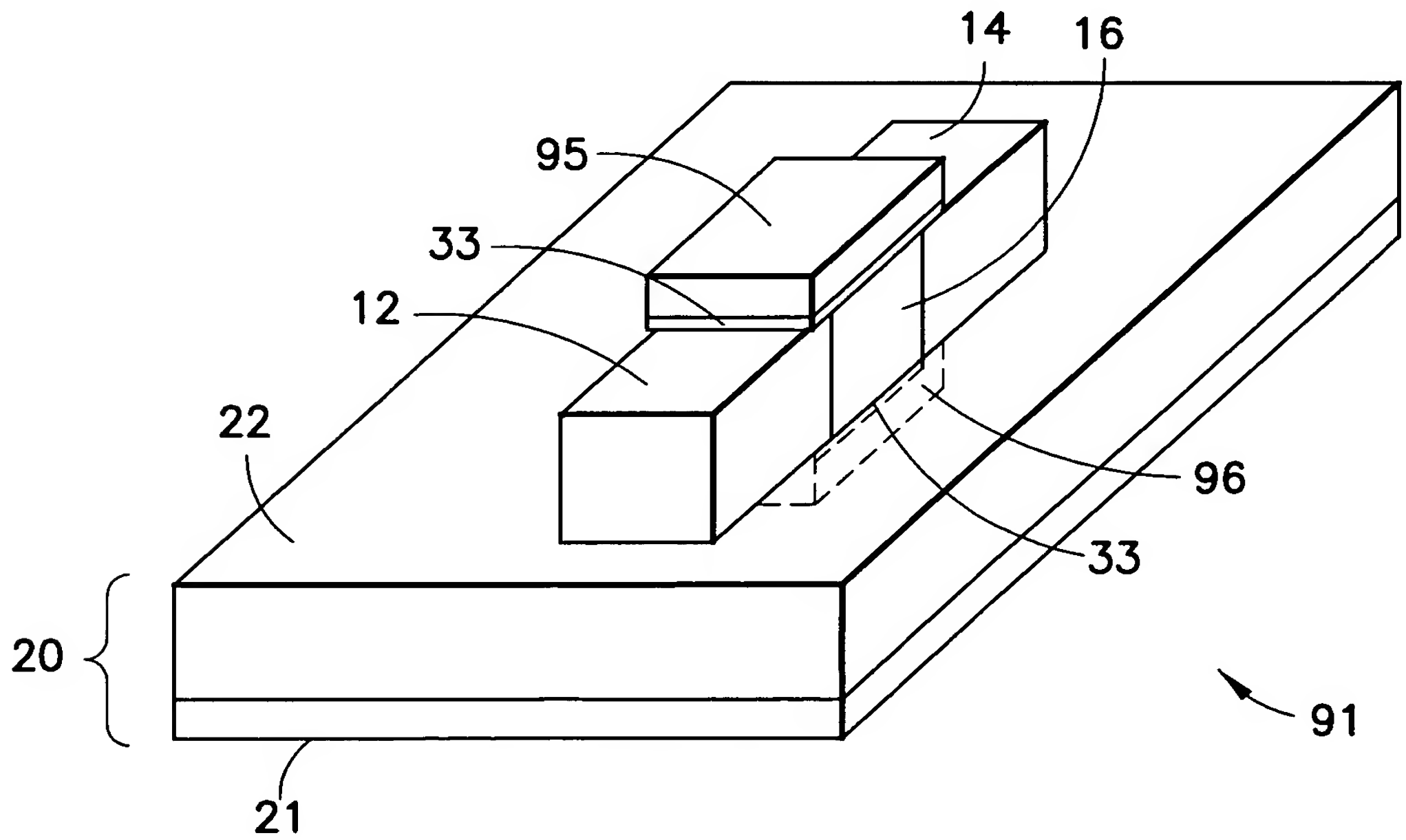


FIG. 8B

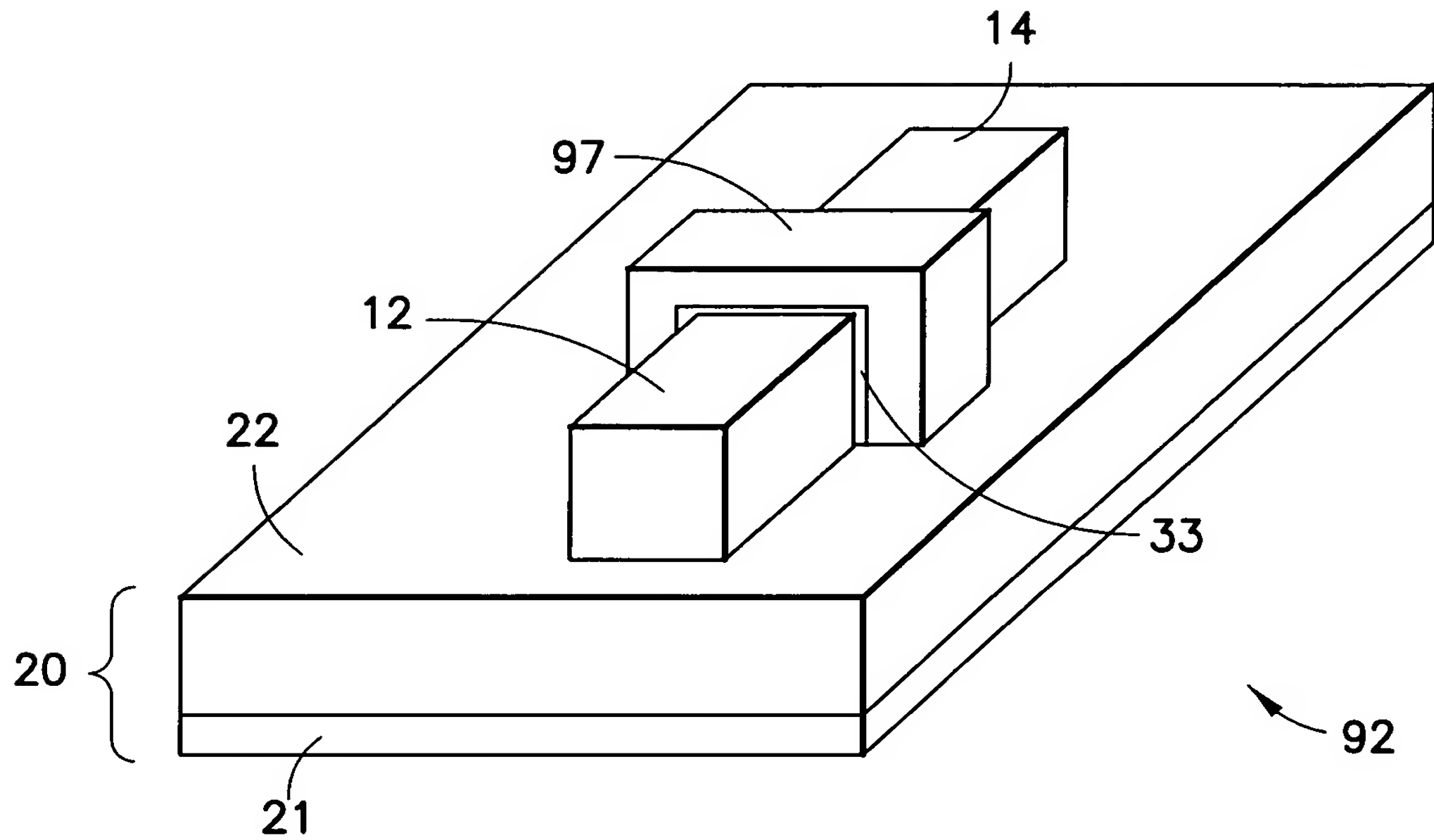


FIG. 8C

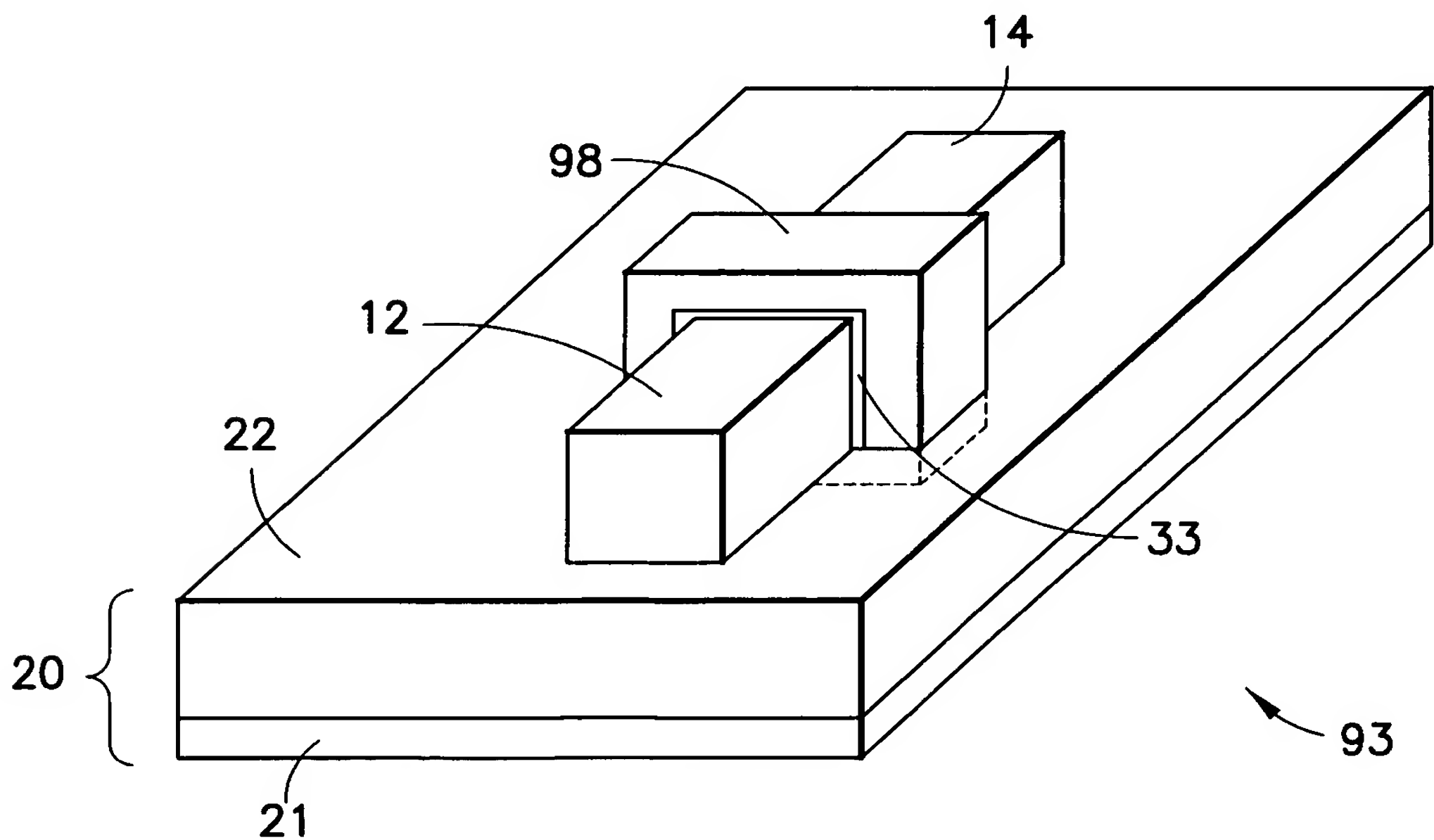


FIG. 8D

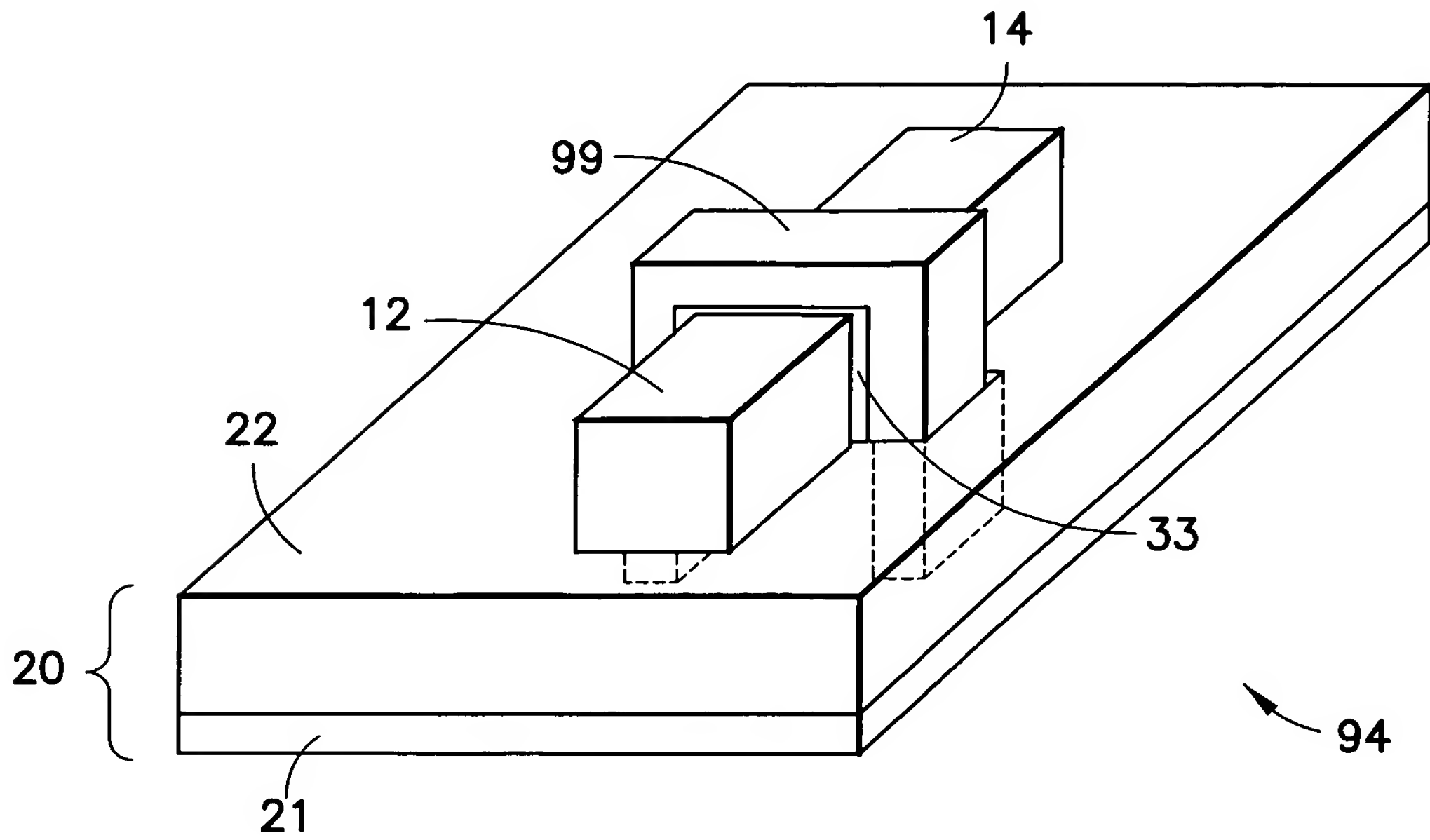


FIG. 8E

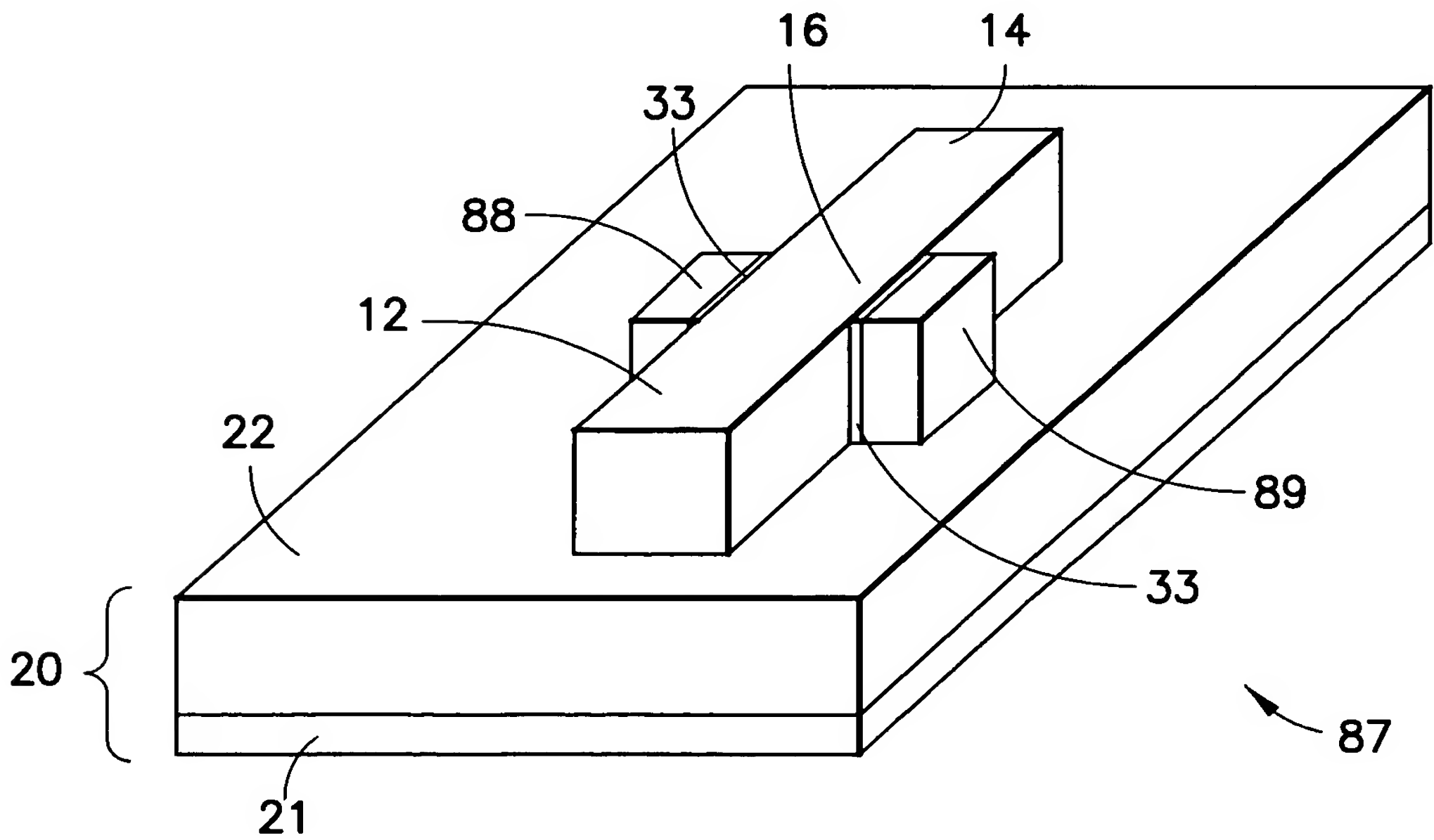


FIG. 8F



